

CVD/ALD process monitoring system (1)  
(The development of the equipments for precursor monitoring)

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This study is about the methodology and equipment for monitoring precursor in chemical vapor deposition (CVD) systems. Since precursor costs are significant, finding an efficient method to monitor precursor is necessary.

The monitoring system involves precursor consumption, vapor pressure and decomposition.

One example is the use of non-contact ultrasonic sensors for determining the liquid level in a container. In this study, sensors based on ultrasonic techniques have been developed to monitor the precursor consumption in a CVD system. Furthermore, the equipments for measuring vapor pressure and decomposition of precursor were fabricated and tested in various ways for the possibility of future applications.